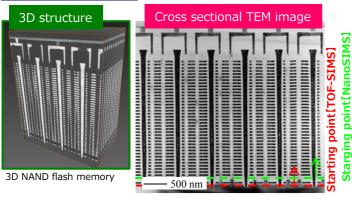
NanoSIMS Analysis of 3D NAND Flash Memory

The NanoSIMS 50L can provide the highest lateral resolution among secondary ion mass spectrometry and can simultaneously achieve high detection sensitivity and high mass resolution. Here, we introduce examples of measuring 3D NAND flash memory using TOF-SIMS and NanoSIMS.

Sample structure



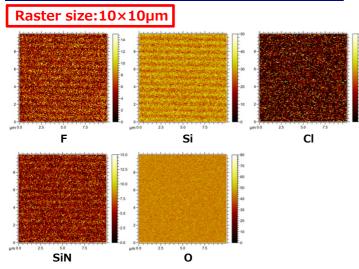
After thinning the Si substrate, SIMS analysis was performed from the backside to the frond-side surface

Instrumental features

Instrument	TOF-SIMS (Depth)	NanoSIMS 50L
Analysis area	Several µm- 300µm□	Several µm- 50µm□
Lateral resolution	5μm (0.Xμm*)	50nm-
Depth resolution	1-5nm	20nm
Analysis depth	Several nm-µm	Several 10nm- 1µm
Detection limit	ppm	ppb-ppm
Mass resolution	$m/\triangle m = \sim 4000$ (300*)	m/△m=4000~
Number of elements detected	All elements	7**

*In the high lateral resolution mode of TOF-SIMS, mass resolution is about 300.
**In some cases, combination of elements might be restricted.

TOF-SIMS analysis results



NanoSIMS analysis results

1E+6
Raster size : 10×10μm

1E+5

1E+4

1E+3

1E+2

1E+1

1E+0

0

200

400

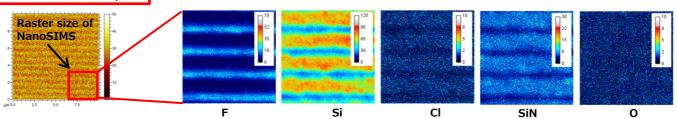
600

800

Cycles

A feature of TOF-SIMS is simultaneous measurement of all elements (qualitative analysis). As a result of the qualitative analysis, fluorine and chlorine were detected as characteristic elements.

Raster size:3×3µm



Secondary ion images are obtained at higher lateral resolution and sensitivity in a small area compared with TOF-SIMS analysis.

When analyzing a small area, it is important to use TOF-SIMS and NanoSIMS properly according to the purpose.